

IN THE CLAIMS:

Please cancel claims 7 and 22-37 without prejudice, add new claims 38-40, and amend the claims as follows:

1. (Currently amended) An apparatus for material deposition on a glass substrate, comprising:

a chamber;  
a process gas distribution assembly within the chamber;  
a power source coupled to the chamber for establishing a plasma; and  
a movable substrate support member within the chamber having a glass support surface thereon, the glass support surface comprising ~~and~~ a thermally insulating layer ~~on the support surface~~ to support a the glass substrate thereon.

2. (Currently amended) The apparatus of claim 1, wherein the process gas distribution assembly comprises a gas dispersion plate ~~further comprises~~ having a heat reflective surface proximate the glass substrate.

3. (Original) The apparatus of claim 1, wherein the substrate support member comprises a heater.

4. (Currently amended) The apparatus of claim 1, wherein the thermally insulating layer comprises ~~at least a first sheet and a second sheet bonded together to form a unified body~~ aluminum nitride.

5. (Currently amended) The apparatus of claim 1, wherein the thermally insulating layer is formed on the substrate support surface member.

6. (Currently amended) The apparatus of claim 1, wherein the thermally insulating layer is selected from the group consisting of ~~insulators, semi-conductors, and combinations thereof~~ aluminum nitride, aluminum oxide, and

combinations thereof.

7. (Cancelled)

8. (Currently amended) The apparatus of claim 1, wherein the thermally insulating layer is bonded to the ~~support surface of the~~ substrate support member.

9. (Original) The apparatus of claim 8, wherein the bond is an adhesive bond.

10. (Currently amended) The apparatus of claim 1, further comprising a frame to hold the thermally insulating layer on the glass supporting surface of the substrate support member.

11. (Currently amended) The apparatus of claim 10, wherein the frame further comprises:

a longitudinal portion having a roof portion and a base, wherein the base is adapted to contact the thermally insulating layer.

12. (Currently amended) An apparatus for material deposition on a glass substrate, comprising:

a chamber;

a process gas distribution assembly within the chamber;

a power source coupled to the chamber for establishing a plasma;

a movable substrate support member within the chamber having a glass support surface thereon, the glass support surface comprising ~~and~~ a thermally insulating layer ~~on the support surface~~ to support a the glass substrate thereon; and

a frame disposed on the thermally insulating layer that when raised by the movable substrate support to a processing position is electrically insulated from the chamber.

13. (Currently amended) The apparatus of claim 12, wherein the process gas distribution assembly comprises a gas dispersion plate ~~further comprises~~ having a heat reflective surface proximate the glass substrate.

14. (Original) The apparatus of claim 12, wherein the substrate support member comprises a heater.

15. (Currently amended) The apparatus of claim 12, wherein the thermally insulating layer comprises ~~at least a first sheet and a second sheet bonded together to form a unified body~~ aluminum nitride.

16. (Currently amended) The apparatus of claim 12, wherein the thermally insulating layer is selected from the group consisting of ~~ceramic, glass, polymer, and combinations thereof~~ aluminum nitride, aluminum oxide, and combinations thereof.

17. (Original) The apparatus of claim 12, wherein the frame when placed in a processing position is positioned proximate the chamber sidewalls to minimize plasma leakage between the sidewalls and the frame during processing.

18. (Original) The apparatus of claim 12, wherein the frame is positioned adjacent a plurality of chamber sidewalls such that a gap is formed to prevent arcing between the frame and the chamber sidewalls.

19. (Currently amended) The apparatus of claim 12, wherein the frame further comprises:

a longitudinal portion having a roof portion and a base, wherein the base is adapted to contact the thermally insulating layer.

20. (Currently amended) The apparatus of claim ~~12~~ 1, wherein the thermally

insulating layer ~~is selected from the group of insulators, semi-conductors, and combinations thereof~~ comprises at least a first sheet and a second sheet bonded together to form a unified body.

21. (Currently amended) The apparatus of claim 12, wherein the thermally insulating layer is selected from the group of ceramic, glass, polymer, and combinations thereof comprises at least a first sheet and a second sheet bonded together to form a unified body.

22-37. (Cancelled)

38. (New) The apparatus of claim 19, wherein the frame is adapted to not contact the glass substrate during processing.

39. (New) The apparatus of claim 38, wherein the frame is adapted to not obscure any portion of the glass substrate during processing.

40. (New) The apparatus of claim 19, wherein at least part of the longitudinal portion of the frame that contacts the thermally insulating layer is rounded.